

Page 7, between lines 17 and 18, insert --BRIEF DESCRIPTION OF THE DRAWINGS--; and between lines 27 and 28, insert --DESCRIPTION OF THE PREFERRED EMBODIMENTS--.

Page 10, line 16, insert --(0.69 MPa)-- before "pressure".

IN THE CLAIMS

Please amend the claims as follows:

1. (Amended) A process for depositing a coating comprising tungsten oxide on the surface of a glass substrate by directing a gaseous stream comprising tungsten oxyhalide or tungsten chloride and a source of oxygen on to the surface of the glass substrate, wherein the glass substrate is at a temperature in the range 500°C to 720°C.

Claim 3, line 1, delete "or claim 2".

Claims 4, 5, 8, 9, 10, 12, 15, 17, 18, 19 and 23, line 1, delete "any preceding" and insert --1-- after "claim".

Claim 7, line 1, delete "or 6".

Claim 14, line 1, delete "or 13".

20. (Amended) A process for coating glass comprising directing a gaseous stream containing a tungsten compound and a source of oxygen on to the surface of a glass substrate thereby forming a non-stoichiometric tungsten oxide layer [characterised in that] wherein the tungsten oxide layer is [non-stoichiometric and the tungsten oxide layer is] overcoated with a further layer.

Claim 21, line 1, delete "19 or".

Claim 22, line 1, delete "claims 19 to 21" and insert --claim 20-- after "to".

Delete original claims 24 to 33 and insert the following new claims:

34. A process according to claim 1 wherein the glass substrate is at a temperature in the range 565°C to 655°C.

35. A process according to claim 1 wherein the tungsten oxide layer is deposited on to coated glass.

36. A process according to claim 35 wherein the coated glass has a coating comprising silicon oxide.
37. A process according to claim 36 wherein the coating comprising silicon oxide further contains carbon.
38. A process for coating glass comprising entraining a tungsten compound in a gas by flowing the gas over a tungsten compound at a temperature below its melting point and directing the gaseous stream on to the surface of a glass substrate thereby forming a tungsten oxide layer, wherein the glass substrate is at a temperature in the range of 500°C to 720°C.
39. A process according to claim 38 wherein the tungsten compound is tungsten halide, tungsten oxyhalide or tungsten carbonyl.

40. A method of coating glass comprising
- (a) providing a glass substrate having a temperature in the range of 500°C to 720°C,
  - (b) preparing a gaseous stream comprising a source of oxygen and a tungsten compound selected from the group consisting essentially of tungsten oxyhalide and tungsten chloride, and
  - (c) directing the gaseous stream on to the glass substrate, thereby depositing a coating comprising tungsten oxide on the glass substrate.

41. A process for depositing a coating comprising tungsten oxide on the surface of a glass substrate by directing a gaseous stream comprising tungsten oxyhalide or tungsten chloride and an ester on to the surface of the glass substrate.

42. A coated glass produced by a process according to claim 1.

43. A multiple glazing unit comprising a coated glass according to claim 42 in spaced opposed relation to a glazing pane.
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